## DATA SHEET



# **GAS MIXER GA-MI-2.1 - PPM**

On-site parts-per-million mixtures of pure gases





### SPECIFICATIONS

#### **FLOW REGULATOR**

measurement principle

thermal mass flow

pressure

0.2 - 10 bara

temperature

0-50°C

accuracy

± 0.3 % EV

+ ± 0.5% MV

measurement

0-400ln/min (depending on the application)

**dynamics** 1:100

**ANALYSIS** 

CO2

Non Dispersive IR, dual wavelength

**O2** 

Potentiometric zirconia sensor

H2 or He

MEMS-density sensor

SYSTEM

size

typical 600x800 mm

weight

typical 20 kg

protection type

IP40

gas connections

typical 6-12 mm Parker A-lock, optional imperial connections

power supply

100-240 VAC, 50-60 Hz communication

Ethernet, USB, GSM-module

for remote access

**APPLICATIONS** 

Welding

**Biotech** 

R&D

Microelectronics

Medical engineering

Art

**Food and Beverage** 



## COMMUNICATION OF TODAY

The **GA-MI-2.1** is a high-quality gas mixer for the production of precise and stable gas mixtures in the trace gas range. A typical application is the production of forming gas Argon with 200 ppm O2 content for aluminium welding processes. Furthermore the GA-MI has an integrated sensor which detects even the slightest deviations of the desired mixing ratio. It forwards an alarm to the selected users. A special character of the GA-MI is its precision even at low flow rates.



The gas mixer works with fully electronic thermal mass flow controllers. These guarantee high accuracy, stable control and high repeatability. The very high dynamic of the flow controllers allow mixtures in the range from 50ml/min up to 400l/min with constant accuracy.



Depending on the system, it is possible to work with a buffer tank or at the point of use. With pressure controlled buffer storage, a vessel is constantly kept above a defined minimum pressure to ensure the required quantity. The automatic switch function is controlled via the differential pressure.